L Number	Hits	1,	DB	Time stamp
1	75287	planarization or polishing or lapping or	USPAT	2003/10/31 14:56
Ĭ		abrading	1	
2	5296	'F	USPAT	2003/10/31 14:59
		abrading) and (sens\$3) same (thermocouple		
		temperature ir infrared optical)		
3	2725		USPAT	2003/10/31 15:00
		abrading) and (sens\$3) same (thermocouple		
		temperature ir infrared optical)) and		
	<u> </u>	(wafer semiconductor)		1
4	16724	/ 'brassarrage or berrewing of rebbrud of	USPAT	2003/10/31 15:00
	1	abrading) and((sens\$3) or (thermocouple		
		temperature ir infrared optical)) same	}	
		(platen \$4table pad cloth)	ļ	İ
5	7077		USPAT	2003/10/31 15:01
	1	abrading) and (sens\$3) or (thermocouple		1
		temperature ir infrared optical)) same		
		(platen \$4table pad cloth)) and (wafer		1
	1213	semiconductor) (((planarization or polishing or lapping	I TODAM	0000 (00 (00 00 00
	1213	or abrading) and ((sens\$3) or	USPAT	2003/10/31 15:08
		(thermocouple temperature ir infrared		
	1	optical)) same (platen \$4table pad cloth))	(ĺ
		and (wafer semiconductor)) and (451/\$		
		156/345.\$)		
7	47		USPAT	2003/10/31 15:14
	7'	same (ir infrared thermocouple	USPAI	2003/10/31 15:14
		temperature) same (polish\$3 abrad\$3 lap\$4		
'	Í	planarization)		[
8	439		USPAT	2003/10/31 15:33
		(ir infrared thermocouple temperature)	551737	2000/10/01 10:55
9	128	156/345.14 156/345.15	USPAT	2003/10/31 15:38
10	40	156/345.16	USPAT	2003/10/31 15:38